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IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF:

Kenichi HIROTA, et al.

: GROUP ART UNIT: 1746

SERIAL NO: 09/700,704

:

FILED: NOVEMBER 24, 2000

: EXAMINER: KORNAKOV, M.

FOR: CLEANING SOLUTION AND CLEANING METHOD FOR COMPONENT OF  
SEMICONDUCTOR PROCESSING APPARATUS

AMENDMENT AND REQUEST FOR RECONSIDERATION

ASSISTANT COMMISSIONER FOR PATENTS  
WASHINGTON, D.C. 20231

SIR:

In response to the Office Action mailed October 2, 2002, Applicants request reconsideration of the above-identified application in view of the following amendment and remarks.

IN THE CLAIMS

Cancel Claims 13-18.

Please amend the claims as follows:

Sub C  
B 1  
1. (Twice Amended) A cleaning solution for removing a byproduct derived from a decomposed substance of a process gas containing C and F, and deposited on a component in a process chamber of a semiconductor processing apparatus for subjecting a target substrate to a semiconductor process with the process gas, the cleaning solution comprising N-methyl-2-pyrrolidone, ethylene glycol monobutyl ether, a surfactant, and water.

B 2  
3. (Twice Amended) The cleaning solution according to claim 1, wherein the water concentration is 5 to 20 wt%.